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(21) International Application Number: PCT/US98/03426 (22) International Filing Date: 23 February 1998 (23.02.98) (30) Priority Data: 08/813,098 7 March 1997 (07.03.97) US (71) Applicant: HOECHST CELANESE CORPORATION [US/US]; Route 202-206 North, Somerville, NJ 08876 (US). (72) Inventors: ASLAM, Mohammad; 7221 Diamond Ridge, Cor- pus Christi, TX 78413 (US). SHEEHAN, Michael, T.; 3117 Briarhurst, Corpus Christi, TX 78414 (US). KUILA, Deba- sish; 4434 Silver Hollow, Corpus Christi, TX 78413 (US). (74) Agents: GENOVA, John, M. et al.; Hoechst Celanese Corpo- ration, Patent Dept., 86 Morris Avenue, Summit, NJ 07901 (US).	(81) Designated States: CN, JP, KR, SG, European patent (AT, BE, CH, DE, DK, ES, FI, FR, GB, GR, IE, IT, LU, MC, NL, PT, SE). Published <i>With international search report.</i>	
(54) Title: PROCESS FOR PREPARING PHOTOACTIVE COUMARIN DERIVATIVES		
(57) Abstract Novel processes for the preparation of a new class of coumarin derivatives, which are useful as photoactive compounds in a wide variety of applications including photoresists and other opto-electronic applications, are disclosed and claimed. The process involves a multi-step synthetic method for the preparation of ether, ester, carbonate, or sulfonate derivative of 5-hydroxy, 6-hydroxy, or 7-hydroxy-3-diazo-4-oxo-3,4-dihydrocoumarin starting from the corresponding dihydroxyacetophenone. The compounds formed from the process of the present invention exhibit very high photosensitivity in the deep ultraviolet (DUV) region (ca. 250 nm), and therefore, are useful as photoactive compounds in DUV photoresist formulations.		